

Catalytic Functionalization of Methyl Group on Silicon: Iridium-Catalyzed C(sp³)–H Borylation of Methylchlorosilanes

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Supporting Information

ABSTRACT: A methyl group of methylchlorosilanes undergoes C–H borylation in an iridium-catalyzed reaction with bis(pinacolato)diboron in cyclohexane at 80 °C, giving (borylmethyl)chlorosilanes selectively.

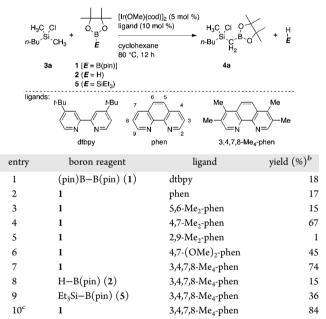
S ince the establishment of Rochow's direct method in the 1940s,¹ methylchlorosilanes (Me_nSiCl_{4-n}, n = 1-3) have been important feedstocks in the industrial production of siliconbased materials including silicone resins, elastomers, and oils. In addition to these oligomers and polymers, a number of organosilicon compounds have been synthesized from methylchlorosilanes and utilized in organic and inorganic synthesis.²In these applications, the conversion of methylchlorosilanes is based on reactions at their Si-Cl bonds, which are efficiently converted into Si-O, Si-N, and Si-C bonds. In contrast, the methyl groups of methylchlorosilanes are always left intact in these conversions, except when radical chlorination gives (chloromethyl)chlorosilanes.³ It would be highly desirable to explore reactions at their methyl groups through catalytic $C(sp^3)$ –H bond functionalization. Although such an innovative transformation has never been shown to date, recent rapid progress in transition-metal-catalyzed C-H bond functionalization may help our exploitation.^{4,5}

In sharp contrast to the catalytic borylation of the $C(sp^2)$ -H bond of aromatic and heteroaromatic compounds using bis(pinacolato)diboron (1) or pinacolborane (2),⁶ much less progress has been made in the catalytic borylation of the $C(sp^3)$ -H bond.⁷ Indeed, the terminal methyl groups of aliphatic hydrocarbons,^{8–10} benzylic methyl groups,^{11–13} and allylic methylenes of cycloalkenes¹⁴ have been reported as limited $C(sp^3)$ –H bonds that can undergo catalytic borylation with high efficiency. Quite recently, borylations of the $C(sp^3)$ -H bonds located β to the oxygen atom of aliphatic cyclic ethers¹⁵ and α to the nitrogen atom of amides, ureas, and 2-aminopyridines¹⁶ have been reported. Herein, we describe an iridium-catalyzed $C(sp^3)$ -H borylation at the methyl groups of methylchlorosilanes to give (borylmethyl)chlorosilanes. The reaction achieves direct catalytic functionalization of methyl groups on silicon,⁵ in which the chlorine acts as a directing group. It is noted that the reaction achieves direct catalytic functionalization of methylchlorosilanes, keeping the chlorine atom at the silicon atom left untouched.

In the course of our attempted reactions of chlorosilanes with boron reagents, we found that a $C(sp^3)$ -H bond of a methyl group on silicon underwent borylation in the presence of a transition metal catalyst. For instance, butylchlorodimethylsilane

(3a, 4 equiv) was reacted with 1 in cyclohexane at 80 °C in the presence of $[Ir(OMe)(cod)]_2$ (5 mol %, 10 mol % Ir) and a ligand (10 mol %) (Table 1). An iridium catalyst bearing 4,4'-di-

Table 1. Screening of Reaction Conditions in C–H Borylation of $3a^{a}$



^a**3a** (0.60 mmol), a boron reagent (0.15 mmol), $[Ir(OMe)(cod)]_2$ (0.0075 mmol), and ligand (0.015 mmol) were stirred in cyclohexane (0.6 mL) at 80 °C for 12 h unless otherwise noted. ^{b1}H NMR yield based on the boron reagent. ^cModified procedure: **1** (0.15 mmol), $[Ir(OMe)(cod)]_2$ (0.0038 mmol), and 3,4,7,8-Me₄-phen (0.0075 mmol) were stirred in cyclohexane (0.6 mL) at 80 °C for 3 min. **3a** (0.60 mmol) was added to the solution, and the resulting mixture was stirred at 80 °C for 12 h.

tert-butyl-2,2'-bipyridine (dtbpy), the most effective catalyst for $C(sp^2)$ —H borylation, ^{6c,d} afforded (borylmethyl)chlorosilane 4a (18% based on 1) selectively with 2 after 12 h (entry 1). It is also noted that the borylation took place selectively at the methyl group with no borylation of the butyl group. This result indicates that the methyl group of 3a underwent C–H borylation under rather mild conditions, even though the methyl group is sterically hindered by the α -branch at the silicon atom. To improve the

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Table 2. Iridium-Catalyze	l C–H Borylation of	Methylchlorosilanes"
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1 (1 oquin)

		1 (1 eq [/r(OMa R ¹ Si ₋ CH ₃ 3 (4 equiv) 80 °C,	e)(cod)] ₂ (2.5 mol %) -Me ₄ -phen (5 mol %) 	R ² CI R ^{1 Si} C ^{- B(pi} H ₂ 4	in) $\xrightarrow{i:PrOH}_{El_3N} \xrightarrow{R^2 S}_{R^1Si}$	D⊁Pr -G ^{-B(pin)} H₂ 6	
entry	silane	product	yield $(\%)^b$	entry	silane	product	yield $(\%)^b$
1	H₃C, CI H₃C ^{, Si} ∼CH₃ 3b	$\begin{array}{c} H_3C, Oi-Pr\\ H_3C, \overset{(Si)}{\sim} C_2^{-B(pin)}\\ H_2 \\ \end{array}$	55 (93) ^c	8 ^d	<i>n</i> -C ₆ H ₁₃ Cl <i>n</i> -C ₆ H ₁₃ S ^Í CH ₃ 3h	$\begin{array}{c} n\text{-}C_6H_{13} & O\text{-}Pr\\ n\text{-}C_6H_{13} & Si \\ H_2 \\ H_2 \\ \textbf{6h} \end{array}$	48
2	H₃Ç ,CI Et ^{∠Si} ∖CH₃ 3c	$\begin{array}{c} H_3C, O^{i\text{-}Pr}\\ \text{Et}^{-Si}, C^{-B(pin)}\\ H_2\\ \textbf{6c} \end{array}$	38 (55) ^c	9	CI_CI H ₃ C ^{_SI} _CH ₃ 3 i	$H_{3}C$ $H_{3}C$ H_{2} $H_{3}C$ H_{2} H_{2} H_{2}	58 (77) ^c
3	H₃CͺCl <i>n</i> -Pr´ ^{Si} ∖CH₃ 3d	$\begin{array}{c} H_3C, O^{J\cdot}Pr\\ n\cdot Pr' \overset{Si}{\sim} C' \overset{B(pin)}{H_2}\\ \mathbf{6d}\end{array}$	80	10	Cl ָCl <i>n</i> -C ₆ H ₁₃ ^{_Si} ∖CH ₃ 3j	$\begin{array}{c} \text{``PrQ_OL'Pr}\\ n\text{-}C_6H_{13} & \text{Si} & \text{C}^{-B(pin)}\\ H_2 \\ \textbf{6j} \end{array}$	71
4	H₃Ç Çl n-Bu ^{∕ Sí} ∖CH₃ 3a	H₃C, Oi-Pr n-Bu ^{∽Si} , C ^{∽B(pin)} H₂ 6a	82	11	CI, CI CI, Si, CH ₃ 3k	6j ⁱ ·PrO O ⁱ ·Pr Cl Si C B(pin) 6k	70
5	H ₃ C Cl <i>n</i> -C ₈ H ₁₇ Si 3e	$\begin{array}{c} H_3C, O^{i\text{-}Pr}\\ h_3C, O^{i\text{-}Pr}\\ h_2 \\ Si \\ Ge \end{array}$	83	12		6k	72
6	H₃C, CI CI ∕ ŠÍ ́CH₃ 3f	$\begin{array}{c} H_3C, Oi\text{-}Pr\\ Cl \searrow Si_{C} B(pin)\\ H_2\\ 6f \end{array}$	60	13	H ₃ C CI H ₃ C CI H ₃ C Si CH ₃ CI CH ₃ 3m	$\begin{array}{c} H_3C, O^{i\text{-}Pr}\\ H_3C, Si \longrightarrow Si, C^{-}B(\text{pin})\\ \text{i-PrO'CH}_3 & H_2\\ \mathbf{6m}\end{array}$	81
7 ^d	H₃C, CI	67 H ₃ C, O <i>i</i> -Pr Si, C ^{, B} (pin) H ₂ 6g	51	14	H₃C H₃C Cl∼śi, Cl H₃C O [,] Si, CH₃ 3n	H ₃ C H ₃ C _O , Pr ^{i-PrO} , Śi, O [,] Śi, C ^{, B} (pin) H ₃ C H ₂ 6n	67

^a1 (0.30 mmol), $[Ir(OMe)(cod)]_2$ (0.0075 mmol), and 3,4,7,8-Me₄-phen (0.015 mmol) were stirred in cyclohexane (1.2 mL) at 80 °C for 3 min. 3 (1.2 mmol) was added to the solution, and the resulting mixture was stirred at 80 °C for 12 h. The product 4 was treated with *i*-PrOH and Et₃N to convert to the isopropoxysilane 6. ^bIsolated yield based on 1. ^{c1}H NMR yield before isolation. ^d10 mol % of Ir-3,4,7,8-Me₄-phen catalyst was used.

yield of 4a, iridium catalysts bearing various 1,10-phenanthroline ligands were examined (entries 2-7). The yield was improved to 67% with a 4,7-dimethyl derivative (4,7-Me₂-phen, entry 4), while the parent 1,10-phenanthroline (phen) and 5,6-dimethyl derivative (5,6-Me₂-phen) gave 4a in low yields (entries 2 and 3). 2,9-Dimethyl-1,10-phenanthroline (2,9-Me₂-phen) completely suppresses the borylation (entry 5). Product 4a was obtained in moderate yield in the presence of 4,7-dimethoxy-1,10-phenanthroline (entry 6). We finally found that an iridium catalyst bearing 3,4,7,8-tetramethyl-1,10-phenanthroline (3,4,7,8-Me₄phen) was most effective for the borylation of 3a with 1, giving 4a in 74% yield (entry 7).¹⁷ Other boron reagents were checked in the reaction of 3a using the Ir-3,4,7,8-Me₄-phen catalyst (entries 8 and 9). Hydroborane 2 also participated in the borylation, although the yield of 4a was low (entry 8). This result indicates that diboron 1 can afford both of the boron atoms for borylation, although incorporation of the second boron atom from 2 is not efficient. We also found that $Et_3Si-B(pin)$ (5)¹³ served as a boron source to give 4a in moderate yield (entry 9). An optimized experimental procedure using 1 and the Ir-3,4,7,8-Me4-phen catalyst was finally established as follows: A cyclohexane solution of [Ir(OMe)(cod)]₂, 3,4,7,8-Me₄-phen, and 1 was prepared and stirred at 80 °C for 3 min. 3a was then added to the solution, and the resulting mixture was stirred at 80 °C. This modified procedure improved the yield of 4a to 84% even with a reduced catalyst loading (5 mol % Ir) (entry 10).

A variety of chlorosilanes 3 were subjected to borylation using 1 in the presence of the Ir-3,4,7,8-Me₄-phen catalyst (Table 2). To avoid handling of the moisture-sensitive chlorosilanes, the borylated products **4** were converted to the corresponding isopropoxysilanes **6** via reaction with *i*-PrOH in the presence of Et₃N. Chlorotrimethylsilane (**3b**) was borylated efficiently to give **6b** in high yield, although the isolated yield dropped because of the instability of **6b** against silica gel column chromatography (entry 1). Borylation of *n*-alkylchlorodimethylsilanes afforded the corresponding products in high yields, except for the reaction of ethyl-substituted **3c**, which gave **4c** in moderate yield (entries 2–5). The reaction was applicable to **3f** bearing a chloromethyl group (entry **6**). Probably because of steric hindrance around the methyl group, borylations of isopropyl-substituted **3g** and dihexyl-substituted **3h** were sluggish, giving borylated **6g** and **6h** in moderate yields by using 10 mol % of the catalyst (entries 7 and 8).¹⁸

Dichloromethylsilane derivatives also underwent borylation (entries 9–12). The reaction of dichlorodimethylsilane (3i) gave the borylated product 6i in good yield after conversion to diisopropoxysilane (entry 9). Dichloromethylsilanes 3j, 3k, and 3l bearing hexyl, 3-chloropropyl, and cyclohexyl groups were effectively borylated to give the corresponding (borylmethyl)-silanes 6j, 6k, and 6l in 70–72% yields (entries 10-12).¹⁸

Substrates including two chlorodimethylsilyl groups were also borylated. Selective monoborylation of 1,2-bis-(chlorodimethylsilyl)ethane **3m** took place to give **6m** in high yield (entry 13). The borylation was applicable to 1,3-dichloro-1,1,3,3-tetramethyldisiloxane **3n** to give **6n** in good yield (entry 14).¹⁸

Borylation of **3i** could be carried out on a multigram scale using a reduced amount of the catalyst (Scheme 1). The borylation took place efficiently using 2 mol % of the Ir-3,4,7,8- Me_4 -phen catalyst to give 6.0 g of 4i (78%) after distillation.

Scheme 1. Multigram Scale Synthesis of 4i Using Lower Catalyst Loading

ରା ପ		[Ir(OMe)(cod)] ₂ (1 mol %) 3,4,7,8-Me ₄ -phen (2 mol %)	
H ₃ C ^{SI} CH ₃	•	cyclohexane (30 mL)	H ₃ C ^{-Si} ,C ^{-B} ,O [∧] H ₂
3i (120 mmol)	(30 mmol)	80 °C, 12 h	4i 6.0 g (23.5 mmol, 78%)

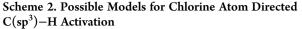
To understand details of the C–H borylation, some substrates were subjected to the borylation conditions using 1 with the Ir-3,4,7,8-Me₄-phen catalyst (Table 3). The reaction of *t*-BuCl (7),

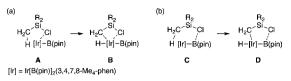
Table 3. Reaction of Various Substrates under C–H Borylation Conditions^{*a*}

entry	substrate	results ^b
1	t-BuCl (7)	no desired product
2	Et ₃ SiCl (8)	no reaction
3	$n-C_{8}H_{17}SiMe_{3}(9)$	no reaction
4	H₃C, OMe <i>n</i> -Bu ^{_Si} ∖CH₃ 10	H ₃ Ç_OMe <i>n</i> -Bu ^{Si} ,C [/] B(pin) H ₂ 11 (< 5%)
5 ^c	H₃C /──CI H₃C ^{/Si} ∖CH₃ 12	$\begin{array}{c} H_{3}C, \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \$
6^d	CD ₃ <i>n</i> -C ₆ H ₁₃ −Si−Cl CH ₃ 3o (4 equiv)	$\begin{array}{c} {}_{C}{\rm D}_{3} & {}_{C}{\rm D}_{2}{\rm B}({\rm pin}) \\ n {}_{C}{\rm G}_{6}{\rm H}_{13} {}_{-}{}^{{\rm S}{\rm I} {}_{-}{\rm O}i {}_{-}{\rm Pr}} & n {}_{C}{\rm G}_{6}{\rm H}_{13} {}_{-}{}^{{\rm S}{\rm I} {}_{-}{\rm O}i {}_{-}{\rm Pr}} \\ {}_{C}{\rm H}_{2}{\rm B}({\rm pin}) & {\rm C}{\rm H}_{3} \\ \end{array} \\ \begin{array}{c} {\rm 6o-H} & {\rm 6o-D} \\ 72\% & ({\rm 6o-H:6o-D} = 73:27) \end{array} \end{array}$
7	H ₃ C, Cl Si CH ₃	$(pin)B \underbrace{\prod_{i=1}^{n} S_{i} S_{i}}_{U} CH_{3}$
	Зр	14 (105%, <i>o</i> : <i>m</i> : <i>p</i> = 0:67:33)

^{*a*}Reactions were carried out at 80 °C according to the procedure described in footnote *a* in Table 2. ^{*b*}Yield based on 1 and isomer ratio were determined by ¹H NMR. ^{*c*}10 mol % of Ir-3,4,7,8-Me₄-phen catalyst was used. ^{*d*}Isolated yield.

a carbon analogue of chlorotrimethlsilane (3b), did not give the desired borylation product at all, indicating that a silicon atom is essential for the C-H borylation (entry 1). As Et₃SiCl (8) resulted in no reaction (entry 2), the C-H borylation takes place selectively at the methyl group on the silicon atom. No reaction took place with trimethyloctylsilane (9) at 80 $^{\circ}$ C (entry 3),¹⁹ while the reaction of butyl(methoxy)dimethylsilane (10) gave the corresponding borylation product albeit in low (<5%) yield (entry 4). It is also noted that the reaction of (chloromethyl)trimethylsilane (12) gave the borylated product 13, although the yield was low (20%, entry 5).²⁰ On the basis of these observations, we propose that the chlorine atom acts as a directing group in the C–H bond activation step in the catalytic cycle.²¹ Indeed, borylation of deuterium-labeled 30 gave a mixture of **60-H** and **60-D** in the ratio 73:27 $(k_{\rm H}/k_{\rm D} = 2.7)$, indicating that cleavage of the C-H bond in the catalytic cycle is involved in the rate-determining step (entry 6). Two possible directing modes can be proposed (Scheme 2): one is coordination of chlorine to the iridium center (A to B), and the other is its coordination to the boron atom bound to the iridium center (C to D). Because the active catalytic species is

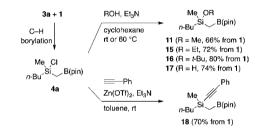




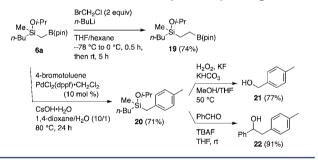
assumed to be Ir[B(pin)]₃(3,4,7,8-Me₄-phen),²² the former may be ruled out in the present C–H borylation due to the vacant coordination site. On the other hand, the latter may be reasonably rationalized on the basis of recent reports on the *ortho*-selective borylation of *N*-(*tert*-butoxycarbonyl)anilines²³ and the β -selective borylation of cyclic ethers.¹⁵ In the reaction of chlorodimethyl(phenyl)silane (**3p**), the borylation took place preferentially at the C(sp²)–H on the phenyl group, leaving the C(sp³)–H of the methyl group untouched (entry 7, Table 3). This result indicates that the directing effect of the chlorine is rather weak.

Synthetic applications of (borylmethyl)chlorosilanes were demonstrated (Schemes 3 and 4). In addition to the conversion

Scheme 3. Conversion of the Chlorine on 4a







to the isopropoxy derivative 6a as shown in Table 2, MeOH, EtOH, t-BuOH, and H₂O reacted with 4a in the presence of triethylamine to give the corresponding (borylmethyl)alkoxysilanes 11, 15, and 16 and silanol 17 in high yields (Scheme 3, top). Reactions of 4a with carbon nucleophiles, such as MeMgI and PhMgBr, resulted in low-yield formation of the desired tetraorganosilanes, probably because attack of the nucleophiles to the boron center took place competitively. We found that successful ethynylation of 4a was achieved by the reaction with ethynylbenzene in the presence of $Zn(OTf)_2$ and Et₃N (Scheme 3, bottom).²⁴ Conversion of the boryl and silyl groups was then examined using 6a as a model substrate (Scheme 4). One-carbon homologation of 6a with ClCH₂Li, which was generated by the reaction of ClCH₂Br with *n*-BuLi, gave (borylethyl)silane 19 in 74% yield (Scheme 4, top).²⁵ A benzylic silane 20 was synthesized in good yield via Suzuki-Miyaura coupling of 6a with 4-bromotoluene using $PdCl_2(dppf)\cdot CH_2Cl_2$ as a catalyst and $CsOH\cdot H_2O$ as a base (Scheme 4, bottom).^{4g} The silyl group of **20** could be utilized for C–O and C–C bond formations,^{26,27} leading to synthesis of alcohols **21** and **22**.

In conclusion, we have established an efficient functionalization of the methyl groups of methylchlorosilanes via iridiumcatalyzed C–H borylation. The reaction is promoted by the directing effect of the chlorine atom on the silicon atom. This catalytic reaction provides a new opportunity to supply organosilicon feedstocks on the basis of conversion of the C– H bond of a methyl group in methylchlorosilanes. In this regard, application of related C–H activation chemistry is currently being pursued in this laboratory.

ASSOCIATED CONTENT

Supporting Information

Experimental details and characterization data of the products. This material is available free of charge via Internet at http:// pubs.acs.org.

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Notes

The authors declare no competing financial interest.

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(17) The efficiency of an Ir-3,4,7,8-Me₄-phen catalyst has also been demonstrated recently in $C(sp^3)$ -H silylation and borylation. See refs 4k and 15.

(18) Double borylated products were not observed at all under the conditions using an excess amount of **3** (4 equiv). When the borylation of **3b** was carried out with 2.2 equiv of **1** in cyclooctane at 110 °C for 12 h, the double borylated Me(*i*-PrO)Si[CH₂B(pin)]₂ (28%) was obtained with **6b** (35%) after treatment with *i*-PrOH/Et₃N.

(19) We found that the reaction of **9** at elevated temperature (110 °C) resulted in formation of a C–H borylated product, (n-C₈H₁₇) Me₂SiCH₂B(pin) (10%). This result indicates that reactivity of the C(sp³)–H bond located α to silicon is increased also by an electronic effect of the silicon atom. See also ref 5b.

(20) No C–H borylation took place with Me₃SiBr and Me₃SiI, while Me₃SiOH resulted in selective O-borylation at the hydroxyl group to form Me₃SiOB(pin) (170% yield based on 1).

(21) The directing effect of a chlorine atom has been observed in the *ortho*-selective C-H borylation of chlorobenzenes using a silicasupported phosphine-iridium catalyst. Kawamorita, S.; Ohmiya, H.; Hara, K.; Fukuoka, A.; Sawamura, M. J. Am. Chem. Soc. **2009**, 131, 5058. (22) (a) Tamura, H.; Yamazaki, H.; Sato, H.; Sakaki, S. J. Am. Chem. Soc. **2003**, 125, 16114. (b) Boller, T. M.; Murphy, J. M.; Hapke, M.;

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